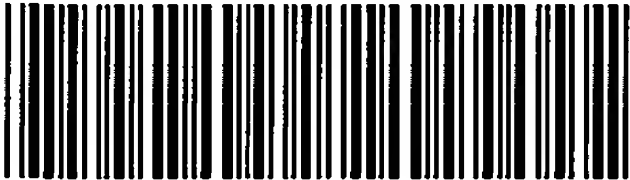


<div>Search Notes</div> <div></div>	Application/Control No.	Applicant(s)/Patent under Reexamination	
	10/617,682	AKUTSU ET AL.	
	Examiner	Art Unit	
	D. Rutledge	2851	

SEARCHED			
Class	Subclass	Date	Examiner
355	53, 67, 72, 75	3/25/2005	DR
250	491.1	3/25/2005	DR
250	492.2	3/25/2005	DR
310	10, 12	3/25/2005	DR

INTERFERENCE SEARCHED			
Class	Subclass	Date	Examiner
355	53,67,75	3/25/2005	DR
250	491.1	3/25/2005	DR
250	492.2	3/25/2005	DR
310 10, 12		3/25/2005	DR

SEARCH NOTES (INCLUDING SEARCH STRATEGY)		
	DATE	EXMR
electron adj beam, plural\$3 or multiple; (wafer or substrate); stage or table; interferomet\$3 or measur\$5;	3/25/2005	DR
position or location or align\$4; rotating or rotation\$2; direction; z adj axis; measuring adj (light or beam) near4	3/25/2005	DR
perpendicular near4 electron adj beam	3/25/2005	DR